CLAIMS

What is claimed is:

7

1

2

1. A laminate circuit structure assembly comprising at least two modularized
circuitized voltage plane subassemblies wherein each of the subassemblies comprise at least
two signal planes having an external and internal surface disposed about an internal voltage
plane; dielectric between the signal and voltage planes; and dielectric on each external
surface of each signal plane; and wherein the subassemblies are bonded together with a
cured dielectric from a composition comprising the same dielectric used in said
subassemblies.

- 1 2. The laminate circuit structure of Claim 1 which further includes an interposer located between the subassemblies wherein the interposer located between the subassemblies comprises dielectric layers disposed about an internal electrically conductive layer.
 - 3. The laminate circuit structure of Claim 1 wherein the dielectric of at least one of the surfaces that is bonded is from said composition.
- 1 4. The laminated circuit structure of Claim 1 wherein vias are disposed within 2 each subassembly for providing electrical communication between signal planes and 3 electrical connection to another subassembly.
- The laminate circuit structure assembly of Claim 4 wherein the vias through the signal planes are plated with a conductive metal.

2 3

1

2

another subassembly.

12.

plated with a conductive metal.

1	6	The low-instead amount atmestices agreembly of Claims 2 with again the internal
1	6.	The laminate circuit structure assembly of Claim 2 wherein the internal
2	electrically co	inductive layer of the interposer is copper.
1	7.	The laminate circuit structure assembly of Claim 2 wherein the interposer is
2	about 3 mils t	o about 10 mils thick.
١.	AH	
ADV.	8.	A method for fabricating a laminate circuit structure assembly which
7	comprises pro	oviding at least two modularized circuitized voltage plane subassemblies
3 4	wherein each	of the subassemblies comprise at least two signal planes having an external
		urface disposed about an internal voltage plane; providing dielectric between
5	the signal and	voltage planes; and providing dielectric on each external surface of each
6	signal plane; a	and providing a non-cured or partially cured curable dielectric composition
7	between the si	ubassemblies wherein the dielectric composition comprises, the same
8	dielectric used	l in said subassemblies, aligning the subassemblies, and then laminating to
9	cause bonding	g of the subassemblies.
1	9.	The method of Claim 8 which further comprises locating an interposer
2	between the si	ubassemblies wherein the interposer comprises dielectric layers disposed about
3	an internal ele	ectrically conductive layer.
1	10.	The method of Claim 9 wherein dielectric of at least one of the surfaces that
2	is to be bonde	d is from said dielectric composition.
1	11.	The method of Claim 8 wherein vias are disposed within each subassembly

The method of Claim 11 wherein the vias through the signal planes are

for providing electrical communication between signal planes and electrical connection to

1	13. The method of claim 11 wherein the vias are filled with conductive	e adhesive.
1	14. The method of Claim 9 wherein the internal electricity conductive	e layer of
2	the interposer is copper.	
1	15. The method of Claim 9 wherein the interposer is about 3 to about	10 mils
2	thick.	
1	16. The method of Claim 8 which comprises providing top	and bottom
2	circuit layers on top and bottom external surfaces of the	assembly.
1	17. The method of Claim 8 wherein the laminating is carried out at	about 100
2	to about 200°C, for about 15 minutes to about 90 minutes, and at a pressure of	about 100
3	to about 500 psi.	
	·	